

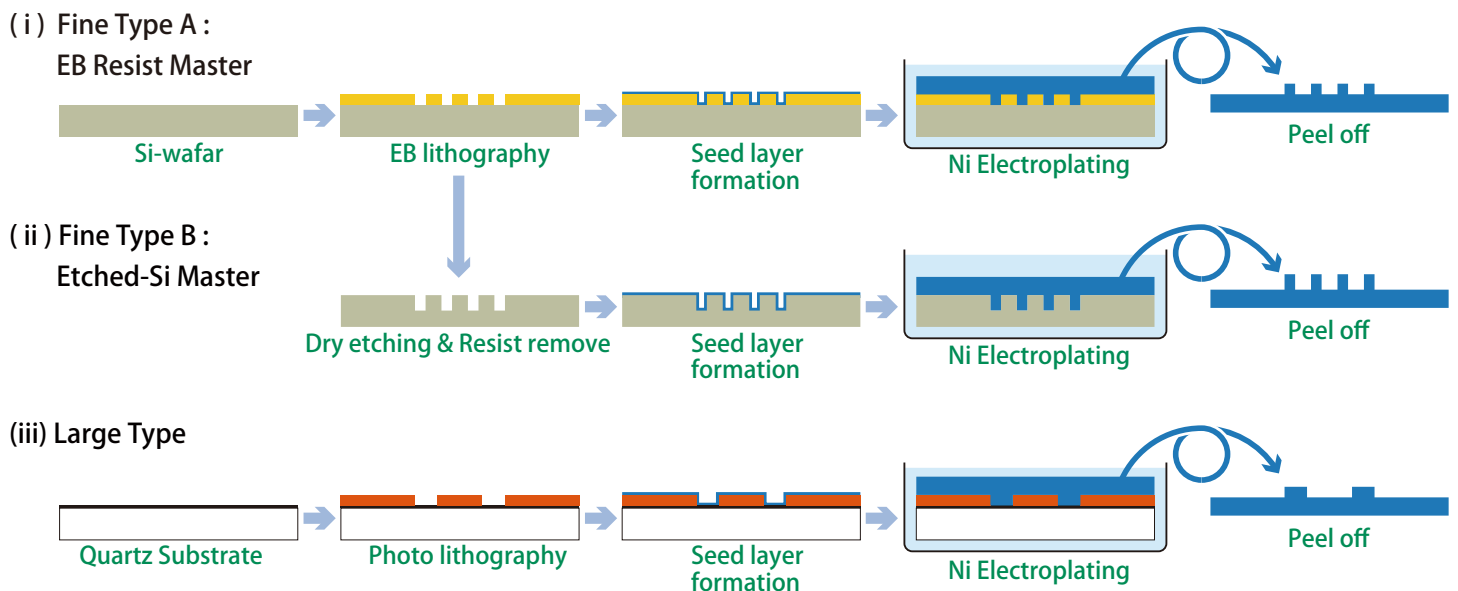
Nanoimprint Lithography Molds

1 Nickel Mold for Thermal Nanoimprint

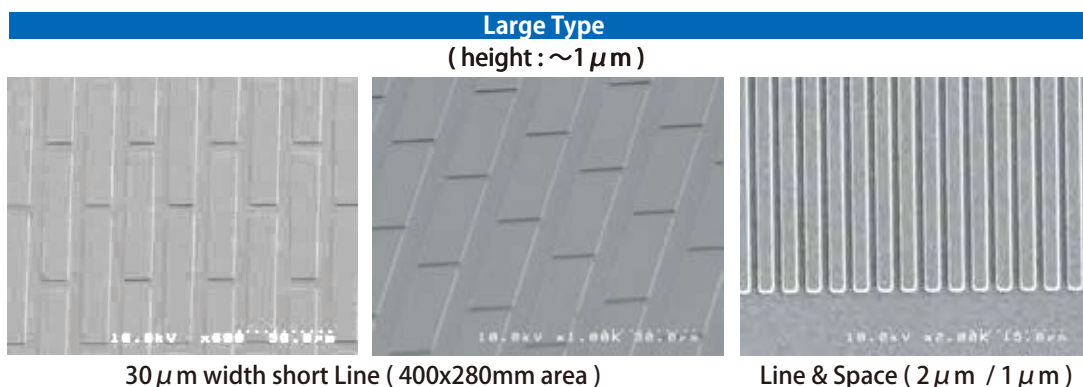
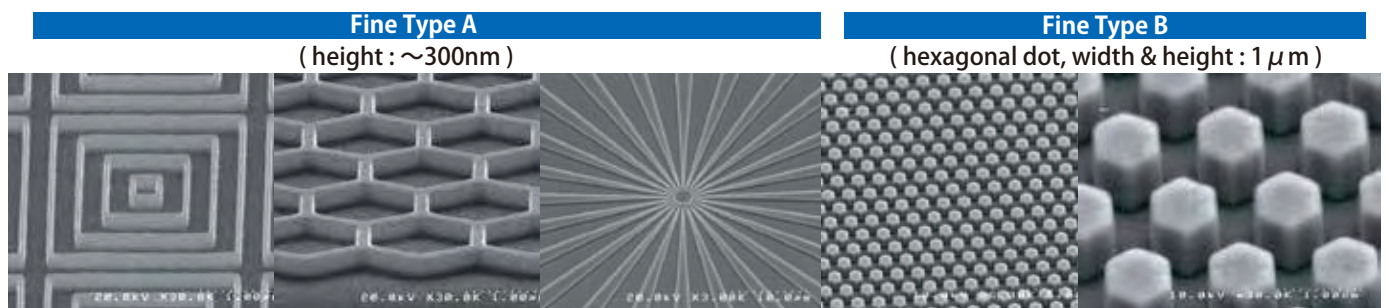
Improvement of fabrication process for Optical Disk Mold

- Advanced Lithography : Fine features, Large area, ...
- Optimization of electroforming process

Mold Fabrication Process



Example of developed structures



2 Quartz Mold for UV Nanoimprint

Using equipment and materials for Photomask fabrication

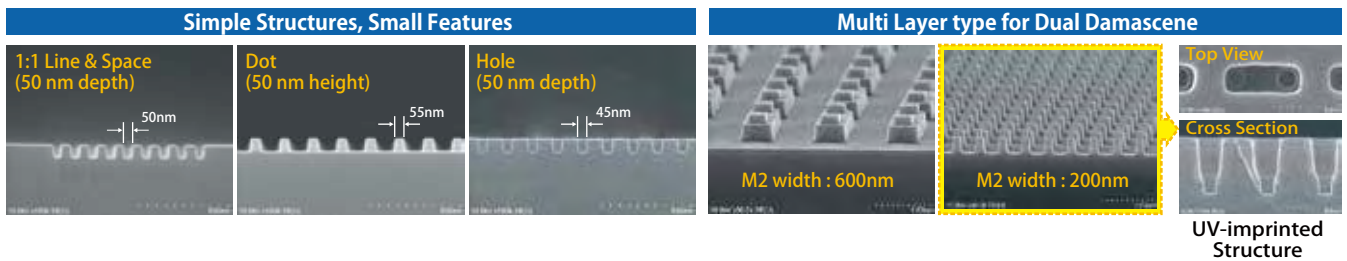
- Max. mold size : 6 inch square

Easy to obtain fine features with good uniformity

Mold Fabrication Process



Example of Quartz structures



3 Silicon Mold for Thermal Nanoimprint

Applying fabrication process of EB Stencil Masks

- Max. mold size : 200 mm diameter

Suitable for high aspect ratio structures

Mold Fabrication Process



Example of Silicon structures

